



Attorney's Docket No. 027260-295

Patent

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13/7DS

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Joint Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: **PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT**

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INFORMATION DISCLOSURE STATEMENT AND CERTIFICATION

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, Applicant hereby submits the following information in conformance with 37 C.F.R. §§ 1.97 and 1.98. Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited in corresponding Korean Office Action dated May 28, 2001, is enclosed.

1. JP 4-5655
2. JP 1-200258

I, the undersigned, hereby certify that each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.

To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned..

Respectfully submitted,

BURNS, DOANE, ~~SWECKER~~ & MATHIS, L.L.P.

By:

Ellen Marcie Emas
Registration No. 32,131

P.O. Box 1404
Alexandria, Virginia 22313-1404
(703) 836-6620

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